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Trifluoromethylation of Alkyl Radicals in Aqueous Solution

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Supporting Information Placeholder

ABSTRACT: The copper-mediated trifluoromethylation of alkyl radicals is described. The combination of $E_{13}SiH$ and $K_2S_2O_8$ initiates the radical reactions of alkyl bromides or iodides with BPyCu(CF₃)₃ (BPy = 2,2'-bipyridine) in aqueous acetone at room temperature to afford the corresponding trifluoromethylation products in good yield. The protocol is applicable to various primary and secondary alkyl halides and exhibits wide functional group compatibility. A mechanism involving trifluoromethyl group transfer from Cu(II)–CF₃ intermediates to alkyl radicals is proposed.

Fluorine is recognized as a key element in pharmaceuticals, agrochemicals and materials. The incorporation of trifluoromethyl groups into organic molecules has a profound effect on their lipophilicity, permeability and metabolic stability. As a consequence, the development of new trifluoromethylation methods that involve mild conditions has received considerable attention and significant progress has been achieved in this area in the past decade.¹⁻³ In particular, a number of methods have been developed for $C(sp^3)$ -CF₃ bond formation. These methods generally fall into the following three categories based on the type of CF₃ intermediates involved: (a) nucleophilic trifluoromethylation with trifluoromethyl anions derived from reagents such as Me₃SiCF₃ (Ruppert–Prakash reagent),⁴ FSO₂CF₂CO₂Me (Chen reagent)⁵ or (Grushin reagent);⁶ (b) (Ph₃P)₃CuCF₃ electrophilic trifluoromethylation² of carbon-centered nucleophiles with electrophilic CF₃ reagents such as the Umemoto reagent,⁷ Togni's reagent⁸ or Shibata reagent;⁹ (c) addition of trifluoromethyl radicals³ to unsaturated moieties such as alkenes, alkynes or isonitriles (Scheme 1, a-c). Although the trifluoromethylation of carbon-centered nucleophiles and electrophiles is well documented, the trifluoromethylation of carbon-centered radicals remains largely unexplored (Scheme 1d). Of the few relevant reports, Gölitz and de Meijere reported that the decomposition of 1-alkyl-2-trifluoromethyldiazenes (R-N=N-CF₃) under UV irradiation in highly viscous solvents, such as t-butanol or hexadecane, led to products of radical coupling (R-CF₃) in low to moderate yield.¹⁰ Furthermore, Qing and coworkers described the copper-mediated 1,2-bis(trifluoromethylation) of alkenes using CF₃SO₂Na and t-BuOOH and involving the addition of CF3 radical to alkenes followed by coupling of the resultant radical with another CF₃ radical.¹¹ Despite these reports, it is important to note that the cross coupling of two transient radicals is unlikely to be general and thus is of limited value in synthesis. Herein we describe a new

protocol for the trifluoromethylation of alkyl radicals that involves CF_3 group transfer.

Scheme 1. Trifluoromethylation for C(sp³)–CF₃ Fromation



A common approach for the generation of alkyl radicals is the treatment of alkyl halides with reducing agents such as tin or silicon hydrides. Thus, we selected 6-bromohexyl tosylate (Br-1a) and triethylsilane as a model system to explore radical trifluoromethylation (Table 1). The use of Br-1a was also designed to help clarify the mechanism of substitution as the tosylate moiety should remain inert under radical trifluoromethylation but should be as reactive as the bromide under nucleophilic trifluoromethylation conditions.^{12, 13} With regard to the CF_3 source, we chose to investigate the use of the complex BPyCu(CF₃)₃ (BPy = 2,2'-bipyridine), recently developed by Grushin et al.¹⁴ Bromide **Br-1a** was treated with excess Et_3SiH and BPyCu(CF₃)₃ in acetonitrile at room temperature in the presence of a peroxide initiator such as di-tert-butyl peroxyoxalate (DBPO), di-tert-butyl peroxide (DTBP), benzoyl peroxide (BPO) or K₂S₂O₈ (entries 1-6, Table 1). Pleasingly, the expected trifluoromethylation product 1a was obtained in 11% yield when $K_2S_2O_8$ was used as the initiator. Switching the solvent to aqueous acetonitrile or acetone significantly increased the yield of the process (entries 7-10, Table 1) and an 80% yield of 1a was obtained when acetone-water (2:1) was employed as solvent. The dramatic, beneficial effect of water may be attributed to the improved solubility of K₂S₂O₈ in aqueous solution. In contrast, no 1a was detected when biphasic CH₂Cl₂/H₂O was used as solvent (entry 11, Table 1). After further adjustment of the reagent ratios (entries 12-16, Table 1), the use of a stoichiometric amount of BpyCu(CF₃)₃ as the CF₃ source and Et₃SiH (6 equiv)/K₂S₂O₈ (4 equiv) as the initiation system, gave 1a in almost quantitative yield (entry 14, Table 1). Use of other silanes in place of Et₃SiH led to lower yields of the product (entries 17-20, Table 1) and the product of direct reduction, n-hexyl tosylate, was obtained in 47%

when (TMS)₃SiH was used. Finally, control experiments indicated that both Et_3SiH and $K_2S_2O_8$ were required for the trifluoromethylation (entries 21 and 22, Table 1). Notably, **1a** was not formed when $Bu_4NCu(CF_3)_4^{14}$ or an electrophilic CF₃ reagent (*e.g.* Tongi's reagent, Umemoto reagent or Shibata reagent) was used in place of BPyCu(CF₃)₃.

Table 1. Optimization of Reaction Conditions

TsO	\sim	Br 40	BPyCu(CF ₃) ₃ (x equiv)	TsO	∠CF3
		DI-10	solvent, rt, 12 h	ia	
ent	х	silane	peroxide	solvent	yield
ryª		(equiv)	(equiv)		(%)
1	2	$Et_3SiH(5)$	DBPO (3)	MeCN	1
2	2	$Et_3SiH(5)$	DTBP (3)	MeCN	4
3°	2	$Et_3SiH(5)$	DTBP (3)	MeCN	9
4	2	$Et_3SiH(5)$	BPO (3)	MeCN	0
5°	2	$Et_3SiH(5)$	BPO (3)	MeCN	49
6	2	$Et_3SiH(5)$	$K_2S_2O_8(3)$	MeCN	11
7	2	$Et_3SiH(5)$	$K_2S_2O_8(3)$	MeCN/H ₂ O (2:1)	65
8	2	$Et_3SiH(5)$	$K_2S_2O_8(3)$	Me ₂ CO/H ₂ O (2:1)	80
9	2	$Et_3SiH(5)$	$K_2S_2O_8(3)$	Me ₂ CO/H ₂ O (4:1)	75
10	2	$Et_3SiH(5)$	$K_2S_2O_8(3)$	Me ₂ CO/H ₂ O (1:1)	30
11	2	Et ₃ SiH (5)	$K_2S_2O_8(3)$	CH ₂ Cl ₂ /H ₂ O (2:1)	0
12	2	Et ₃ SiH (6)	$K_2S_2O_8(3)$	Me ₂ CO/H ₂ O (2:1)	91
13	2	Et ₃ SiH (6)	$K_2S_2O_8(4)$	Me ₂ CO/H ₂ O (2:1)	94
14	1	Et ₃ SiH (6)	$K_2S_2O_8(4)$	Me ₂ CO/H ₂ O (2:1)	98 ^d
15	0.8	Et ₃ SiH (6)	$K_2S_2O_8(4)$	Me ₂ CO/H ₂ O (2:1)	90
16	0.6	Et ₃ SiH (6)	$K_2S_2O_8(4)$	Me ₂ CO/H ₂ O (2:1)	80
17	1	$Et_2SiH_2(6)$	$K_2S_2O_8(4)$	Me ₂ CO/H ₂ O (2:1)	76
18	1	(TMS) ₃ SiH (6	$K_2S_2O_8(4)$	Me ₂ CO/H ₂ O (2:1)	9 ^e
19	1	$Ph_3SiH(6)$	$K_2S_2O_8(4)$	Me ₂ CO/H ₂ O (2:1)	0
20	1	(MeO) ₃ SiH (6	$K_2S_2O_8(4)$	Me ₂ CO/H ₂ O (2:1)	0
21	1	none	$K_2S_2O_8(4)$	Me ₂ CO/H ₂ O (2:1)	0
22	1	Et ₃ SiH (6)	none	Me ₂ CO/H ₂ O (2:1)	0

^a Reaction conditions: **Br-1a** (0.1 mmol), BPyCu(CF₃)₃, silane, peroxide, solvent (3 mL), rt, 12 h. ^{b 19}F NMR yield (with PhCF₃ as the internal standard) based on **Br-1a**. ^c The reaction was carried out under UV (365 nm) photolysis. ^d Isolated yield: 95%. ^e *n*-Hexyl tosylate was isolated in 47% yield.

With the optimized conditions in hand (entry 14, Table 1), we set out to explore the scope of the method. As shown in Scheme 2, the radical trifluoromethylation of various primary alkyl bromides **Br-1** proceeded smoothly in aqueous solution at room temperature and furnished products **1a–1t** in good to excellent yield. The presence of a wide range of functional groups was tolerated by the process. For example, ethers, silyl ethers, ketones, esters, nitriles, amides, imides, sulfonates, sulfonamides, free carboxylic acids, aryl and alkyl chlorides all proved to be compatible with the reaction. This excellent functional group compatibility allows the direct modification of complex molecules such as carbohydrates, as exemplified by the efficient preparation of **1q**. In contrast, primary alkyl chlorides were inert under the reaction conditions. For example, trifluoromethylated alkyl chloride **1m** was obtained in high yield.

We next extended the method to the trifluoromethylation of secondary alkyl bromides (Scheme 3). As for the reaction of primary alkyl bromides, secondary alkyl bromides Br-2 underwent smooth trifluoromethylation under the optimized conditions and gave the expected products of trifluoromethylation 2a-2o in satisfactory yield. Again, broad substrate scope and wide functional group compatibility was observed. Of particular note, trifluoromethylated alkyl azide (2f), amino acid derivative (2j), and steroid (2n) were obtained from the corresponding bromides. thus illustrating the suitability of this method for the late-stage modification of complex molecules. Moderate diastereocontrol was observed in the preparation of the trifluoromethylated products 2j, 2l and 2n. Tertiary (e.g. 2m) and primary alkyl chlorides (e.g. 2k) were unreactive towards trifluoromethylation. Interestingly, when the gem-dibromide substrate (Br-20) was employed, the corresponding mono-trifluoromethylation product 20 was obtained in 83% yield with only a trace of bistrifluoromethylation observed.

Scheme 2. Trifluoromethylation of Primary Alkyl Bromides



^a Reaction conditions: **Br-1** (0.2 mmol), BPyCu(CF₃)₃ (0.2 mmol), Et₃SiH (1.2 mmol), $K_2S_2O_8$ (0.8 mmol), acetone (4 mL), H₂O (2 mL), rt, 12 h. ^b Isolated yield based on **Br-1**. ^c Solvent: acetone (4 mL), H₂O (1 mL).

In addition to being general, the radical trifluoromethylation is operationally simple and the conditions used are extremely mild.

It is also important to note that the few reports of nucleophilic trifluoromethylation of simple alkyl halides either require harsh reaction conditions or suffer from limited substrate scope.¹² Thus, this radical trifluoromethylation approach complements known routes to related targets.

Scheme 3. Trifluoromethylation of Secondary Alkyl Bromides



^a Reaction conditions: **Br-2** (0.2 mmol), BPyCu(CF₃)₃ (0.2 mmol), Et₃SiH (1.2 mmol), K₂S₂O₈ (0.8 mmol), acetone (4 mL), H₂O (2 mL), rt, 12 h. ^b Isolated yield based on **Br-2**. ^c Solvent: acetone (4 mL), H₂O (1 mL). ^d *trans/cis* = 70:30. ^e *trans/cis* = 68:32. ^f dr = 80:20.

Scheme 4. Trifluoromethylation of Alkyl Iodides



^a Reaction conditions: I-1 (0.2 mmol), BPyCu(CF₃)₃ (0.4 mmol), Et₃SiH (1.2 mmol), $K_2S_2O_8$ (0.8 mmol), acetone (4 mL), H_2O (1

mL), UV (365 nm), rt, 12 h. ^b Isolated yield based on I-1. ^c Ar = p-Cl-C₆H₄.

In contrast to primary and secondary alkyl bromides, tertiary alkyl bromides did not give the products of trifluoromethylation. Instead, byproducts presumably derived from the corresponding tertiary alkyl radicals were obtained (see the Supporting Information for details). It is likely that the trifluoromethylation of tertiary alkyl radicals is retarded by steric effects.

We then extended the method to alkyl iodides. Given that alkyl iodides are even more reactive than alkyl bromides towards triethylsilyl radicals,¹⁵ it was surprising to find that the reaction of alkyl iodides under the above optimized conditions produced low yields of the expected trifluoromethylation products ($20 \sim 30\%$) and the alkyl iodides ($60 \sim 70\%$) were recovered. However, reoptimized reaction conditions, involving UV irradiation (365 nm), delivered the expected trifluoromethylation products 1 and 2 in satisfactory yields from the corresponding alkyl iodides I-1. This protocol is applicable to both primary and secondary alkyl iodides (Scheme 4).

Scheme 5. Mechanistic Experiments



$$Ph_{(1)_{4}} \xrightarrow{Br} Br \xrightarrow{BryCu(CF_{3})_{3}} Ph_{(1)_{4}} \xrightarrow{CF_{3}} Ph_{(1)_{4}} (2)$$

$$5 rt, 12 h 6 (25\%)$$

$$BPyCu(CF_3)_3 + Et_3B/O_2 \xrightarrow[rt, 4h]{} Et_7CF_3 \qquad (3)$$

$$Cu(OTf)_{2}/BPy + TMSCF_{3}/CsF + Et_{3}B/O_{2} \xrightarrow{MeCN} Et-CF_{3} \quad (4)$$

$$7 \quad (35\%)$$

$$BPyCu(CF_{3})_{3} + \bigvee_{N=O}^{N=O} \xrightarrow{MeCN}_{365 \text{ nm}} \bigvee_{rt, 4 \text{ h}}^{CF_{3}} (5)$$

To gain further insight into the trifluoromethylation, mechanistic studies were carried out (Scheme 5). The reaction of 2-(Nallyl-N-tosylamino)ethyl bromide (3) under the optimized conditions afforded the cyclized product 4 in 55% yield (Eq. 1). When cyclopropylmethyl bromide 5 was subjected to the optimized conditions for the trifluoromethylation of alkyl bromides, the ringopening product 6 was isolated in 25% yield (5 was recovered in 25% yield) (Eq. 2). These radical clock experiments¹⁶ unambiguously demonstrated the intermediacy of alkyl radicals. To probe the identity of the species responsible for the trifluoromethylation of alkyl radicals, BPyCu(CF₃)₃ was directly treated with ethyl radicals formed from Et₃B under an O₂ atmosphere. The formation of 1,1,1-trifluoropropane (7) was not detected (Eq. 3). In contrast, when a mixture of Cu(OTf)₂, BPy, TMSCF₃ and CsF in 1:1:2.5:2.5 ratio was treated with Et₃B/O₂ in acetonitrile at room temperature, the product 7 was formed (35% yield by ¹⁹F NMR) (Eq. 4). These two experiments suggest that the active

trifluoromethylation agent is likely to be a Cu(II)–CF₃ complex rather than a Cu(III)–CF₃ complex. Finally, the role of UV irradiation in the reactions of alkyl iodides was also probed. As shown in Eq. 5, the photolysis of BPyCu(CF₃)₃ in the presence of an equimolar amount of TEMPO (2,2,6,6-tetramethylpiperidine-*N*-oxyl radical) afforded **8** in 68% yield, indicating that trifluoromethyl radicals are produced from BPyCu(CF₃)₃ upon photostimulation.¹⁷

A plausible mechanism for the trifluoromethylation is shown in Figure 1. Interaction of Et₃SiH with persulfate generates the triethylsilyl radical that abstracts a bromine atom from alkyl bromide to produce the corresponding alkyl radical. Subsequent trifluoromethyl group transfer from a Cu(II)-CF₃ complex (such as A)¹⁸ to the alkyl radical affords the trifluoromethylation product and a Cu(I) complex (such as B). Furthermore, complex A may be regenerated by comproportionation of **B** with BPyCu(CF₃)₃. In the reaction of alkyl iodides, Et₃SiI generated by iodine atom abstraction by the triethylsilyl radical may undergo hydrolysis in aqueous solution to give HI. I2 may then be produced by $K_2S_2O_8$ oxidation of HI, and I_2 may act as the radical chain suppressant.¹⁹ Such a phenomenon is well documented in iodine atom transfer radical addition reactions.¹⁹ Upon UV irradiation, the trifluoromethyl radical is generated and this may serve as a scavenger for I2, forming CF3I, thus allowing the radical trifluoromethylation to proceed smoothly. Further investigations on the mechanism of radical trifluoromethylation are certainly underway.



Figure 1. Proposed mechanism for the trifluoromethylation of alkyl radicals.

In conclusion, we have developed a practical protocol for the trifluoromethylation of alkyl halides formed *in situ* from alkyl halides. As the procedure is operationally simple, broad in scope, tolerant of sensitive functional groups, and utilizes the readily available Grushin reagent BPyCu(CF_3)₃, the method should find application in the synthesis of important trifluoromethylated molecules. A catalytic variant of the radical trifluoromethylation is currently under development in our laboratory.

ASSOCIATED CONTENT

Supporting Information

Full experimental details, characterizations of new compounds, and copies of 1 H, 13 C and 19 F NMR spectra (PDF). The material is available free of charge on the ACS Publications website.

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Notes

The authors declare no competing financial interests.

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